High-rate growth of hydrogenated amorphous and microcrystalline silicon for thin-film silicon solar cells using dynamic very-high frequency plasma-enhanced chemical vapor deposition

Thomas Zimmermann

JÜLICH
FORSCHUNGSZENTRUM

Member of the Helmholtz Association

Forschungszentrum Jülich GmbH
Institute of Energy- and Climate Research (IEK)
Photovoltaics (IEK-5)

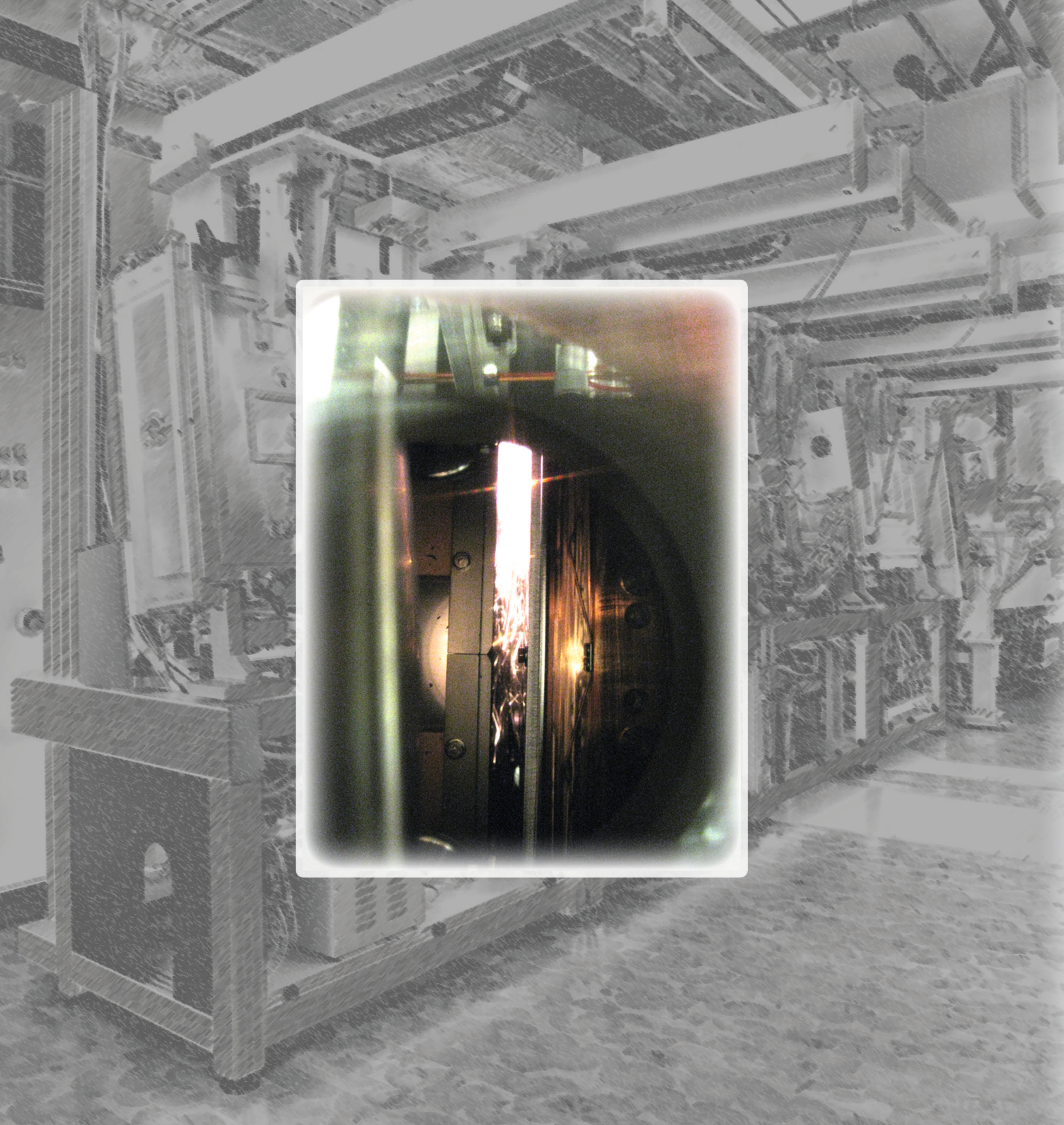
High-rate growth of hydrogenated amorphous and microcrystalline silicon for thin-film silicon solar cells using dynamic very-high frequency plasma-enhanced chemical vapor deposition

Thomas Zimmermann

Schriften des Forschungszentrums Jülich
Reihe Energie & Umwelt / Energy & Environment Band / Volume 183

ISSN 1866-1793 ISBN 978-3-89336-892-1

Contents



Energie & Umwelt / Energy & Environment
Band / Volume 183
ISBN 978-3-89336-892-1

JÜLICH
FORSCHUNGSZENTRUM